

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Kenichiro SATO, et al.

Continuation of Appln. No.: 09/023,801

Group Art Unit: Not yet assigned

Continuation Filed: December 6, 2000

Examiner: Not yet assigned

For: POSITIVE TYPE PHOTORESIST COMPOSITION

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Prior to examination, please amend the above-identified application as follows:

IN THE SPECIFICATION:

Amend the specification by inserting before the first line the sentence:

-- This is a continuation of Application No. 09/023,801 filed February 13, 1998, the disclosure of which is incorporated herein by reference. --

IN THE CLAIMS:

Please cancel claims 1-5 and 10-19.

Please amend claims 6-9 as follows:

6. (Amended) A positive photoresist composition comprising a resin which has an ester group represented by the following general formula (I-2) in its molecule and is